

CONTENTS

CONTRIBUTORS TO VOLUME 54	vii
FOREWORD	ix

Magnetic Reconnection Experiments

P. J. BAUM AND A. BRATEN AHL

I. Prolog	1
II. Introduction	2
III. Historical Perspective Prior to 1970	8
IV. Reconnection Theory	14
V. Reconnection Experiments	22
VI. Discussion and Conclusions	51
Appendix I. A Simple Example of an <i>X</i> Point	55
Appendix II. Reconnection Jargon	57
Appendix III. Impulsive Flux Transfer and Circuit Transients	58
References	61

Electron Physics in Device Microfabrication. II

Electron Resists, X-Ray Lithography, and Electron Beam Lithography Update

P. R. THORNTON

I. Introduction	69
II. Interactions between a Focused Electron Beam and a Resist-Covered Wafer	73
III. X-Ray Lithography	95
IV. Recent Work in Electron Beam Lithography	116
V. The Relative Roles of X-Ray and Electron Beam Lithography Systems with High Throughput	133
References	136

Solar Physics

LAWRENCE E. CRAM

I. Introduction	141
II. The Solar Interior	144
III. The Quiet Solar Atmosphere	160
IV. Solar Activity	179
References	187

Aspects of Resonant Multiphoton Processes

A. T. GEORGES AND P. LAMBROPOULOS

I. Introduction	191
II. Formal Theory of Multiphoton Processes	194
III. The Quantum Theory of Resonant Two-Photon Processes	200
IV. The Effect of Nonresonant States	206
V. Higher-Order Processes	209
VI. Semiclassical Approaches	215
VII. Multiple Resonances	219
VIII. Field Statistics and Bandwidth Effects	224
IX. Experimental Investigations of Resonant Multiphoton Processes	233
References	236

Fundamentals and Applications of Auger Electron Spectroscopy

PAUL H. HOLLOWAY

I. Introduction	241
II. Fundamentals	242
III. Experimental Approach	274
IV. Quantitative AES	280
V. Sample Damage	285
VI. Applications	287
VII. Summary	291
References	292

AUTHOR INDEX	299
SUBJECT INDEX	311